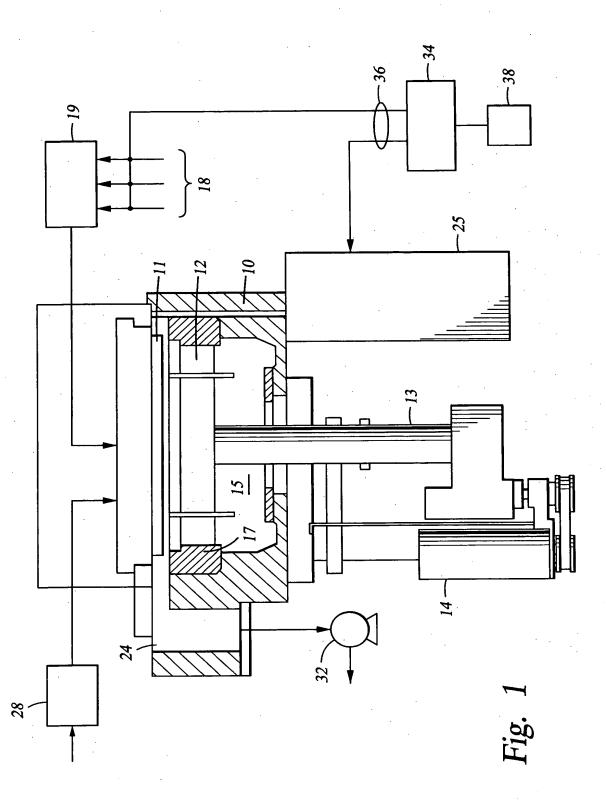
ATTY DKT. NO.: AMAT/2592.C9/DSM/LOW K/JW
U.S. SERIAL NO.: UNKNOWN
FILED: HEREWITH
APPLICANT: APPLIED MATERIALS, INC.
TITLE: METHOD OF DECREASING THE K VALUE IN SIOC LAYER DEPOSITED BY CHEMICAL VAPOR DEPOSITION
INVENTOR: GAILLARD, ET AL.
EXPRESS MAIL NO.: EV335471343US
PAGE 1 OF 7



AMAT/2592.C9/DSM/LOW K/JW

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L

ATTY DKT. NO.: AMAT/2592.C9/DSM/LOW K/JW

U.S. SERIAL NO.: UNKNOWN
FILED: HEREWITH

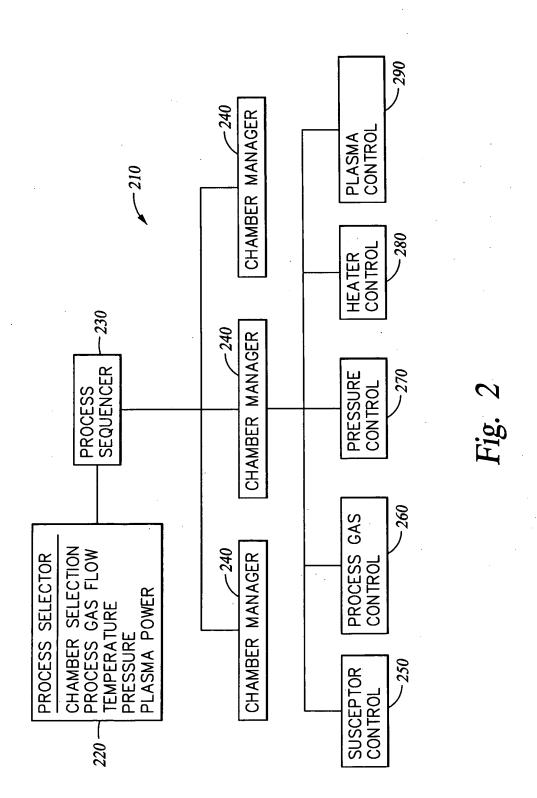
APPLICANT: APPLIED MATERIALS, INC.

TITLE: METHOD OF DECREASING THE K VALUE IN SIOC LAYER
DEPOSITED BY CHEMICAL VAPOR DEPOSITION

INVENTOR: GAILLARD, ET AL.

EXPRESS MAIL NO.: EV335471343US

PAGE 2 OF 7



ATTY DKT. No.: AMAT/2592.C9/DSM/LOW K/JW

U.S. SERIAL NO .: UNKNOWN **HEREWITH** FILED:

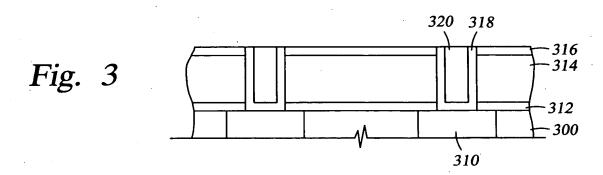
APPLICANT: APPLIED MATERIALS, INC.

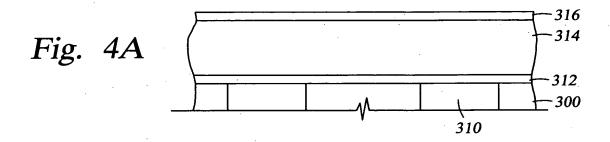
TITLE: METHOD OF DECREASING THE K VALUE IN SIOC LAYER
DEPOSITED BY CHEMICAL VAPOR DEPOSITION

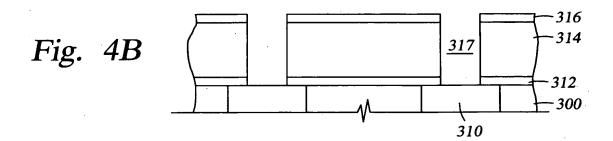
INVENTOR: GAILLARD, ET AL.

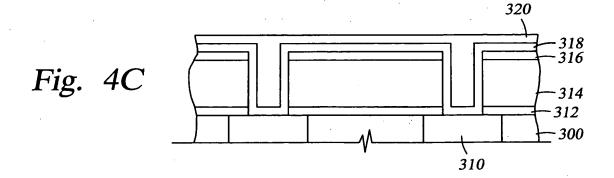
EXPRESS MAIL NO.: EV335471343US

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ATTY DKT. No.: AMAT/2592.C9/DSM/LOW K/JW U.S. SERIAL No.: UNKNOWN

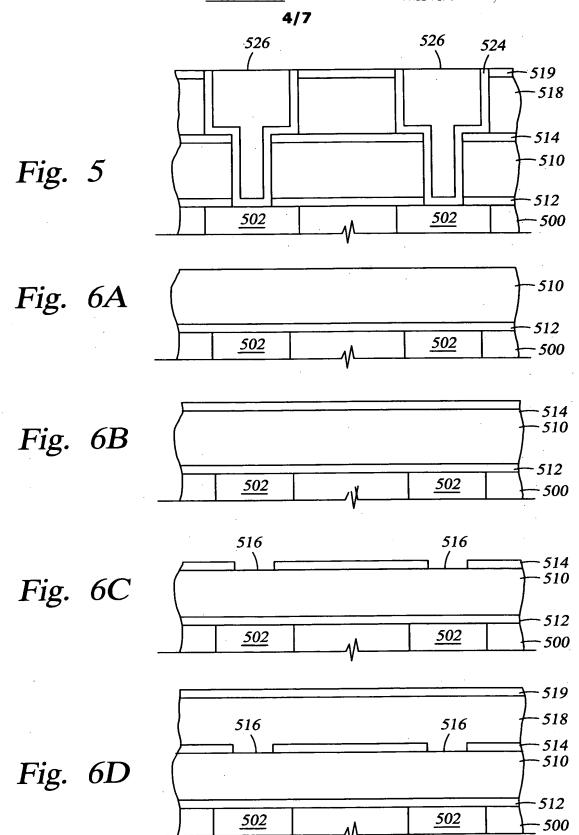
FILED: HEREWITH
APPLICANT: APPLIED MATERIALS, INC.
TITLE: METHOD OF DECREASING

METHOD OF DECREASING THE K VALUE IN SIOC LAYER DEPOSITED BY CHEMICAL VAPOR DEPOSITION

INVENTOR: GAILLARD, ET AL. EXPRESS MAIL NO.: EV335471343US

PAGE 4 OF 7

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U.S. SERIAL NO.: FILED:

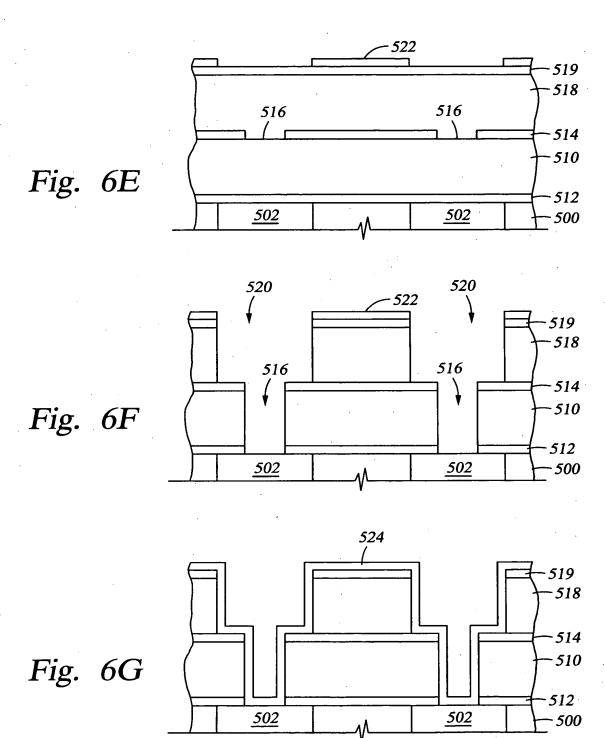
APPLICANT:

APPLIED MATERIALS, INC.
METHOD OF DECREASING THE K VALUE IN SIOC LAYER
DEPOSITED BY CHEMICAL VAPOR DEPOSITION TITLE:

INVENTOR: GAILLARD, ET AL. EXPRESS MAIL NO .: EV335471343US

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ATTY DKT. No.: U.S. SERIAL No.:

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APPLICANT:

AMAT/2592.C9/DSM/LOW K/JW
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APPLIED MATERIALS, INC.
METHOD OF DECREASING THE K VALUE IN SIOC LAYER
DEPOSITED BY CHEMICAL VAPOR DEPOSITION
CALLADD. ETA. TITLE:

INVENTOR: GAILLARD, ET AL. EXPRESS MAIL NO.: EV335471343US

PAGE 6 OF 7

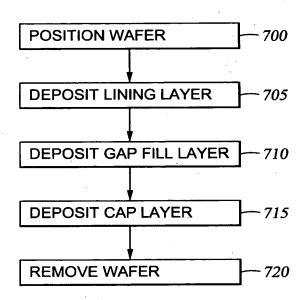


Fig. 7

ATTY DKT. NO.: AMAT/2592.C9/DSM/LOW K/JW U.S. SERIAL NO.: UNKNOWN HEREWITH

APPLICANT:

APPLIED MATERIALS, INC.
METHOD OF DECREASING THE K VALUE IN SIOC LAYER
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INVENTOR: GAILLARD, ET AL. EXPRESS MAIL NO.: EV335471343US

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